			IND.	Time stamp
L	Hits	Search Text	DB	Time stamp
Number				2002/02/10
-	215	polysilicon same (pores asperit\$3)	USPAT	2003/03/19
				11:07
-	5677	mask near3 alignment	USPAT	2003/03/19
				11:06
_	3996	(mask near3 alignment) and etch\$3	USPAT	2003/03/19
				10:34
l _	479	(mask near3 alignment) and etch\$3 near2	USPAT	2003/03/19
		(poly polysilicon)		11:07
	56		USPAT	2003/03/19
		(poly polysilicon)) and mark\$1		11:06
l _	4522	mask near3 alignment	US-PGPUB;	2003/03/19
-	4322	mask fieals allgiment	EPO; JPO;	11:07
			DERWENT	11.07
	0	(mask near3 alignment) and mark\$1 and	USPAT	2003/03/19
-	U	etch\$3 near2 (poly polysilicon)	USFAL	11:07
	9		US-PGPUB;	2003/03/19
_	9	(Mass nears arrangement)	EPO; JPO;	11:07
		etch\$3 near2 (poly polysilicon)	,	11:07
		(500 500 500 500 500 500 500 500 500 50	DERWENT	2002/02/10
-	2485	438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
				11:08
-	342	438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
		and ion near implantat\$3		11:10
-	338	(438/703,704,706,712,719,720,723,724.ccls.	USPAT	2003/03/19
		and ion near implantat\$3) and etch\$3	·	11:10
-	7666	430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19
				11:09
-	414	216/47.ccls.	USPAT	2003/03/19
				11:10
_	7940	430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19
1		216/47.ccls.		11:10
-	454		USPAT	2003/03/19
		216/47.ccls.) and ion near implantat\$3		11:10
_	435	((430/311-314,323-326,329,281.1.ccls.	USPAT	2003/03/19
		216/47.ccls.) and ion near implantat\$3)		11:10
		and etch\$3		
l _	419		USPAT	2003/03/19
		216/47.ccls.) and ion near implantat\$3)	:	11:15
		and etch\$3) not		
		((438/703,704,706,712,719,720,723,724.ccls		
1		and ion near implantat\$3) and etch\$3)		1
_	1	I =	USPAT	2003/03/19
	1	, 020000 /.2		11:15
_	5	("4068018" "4253888" "4321317"	USPAT	2003/03/19
-		(4060016	001111	11:15
L	L_,	3003120 0001133 J.EN.	L	1